

**Process for producing opaque quartz glass, SiO₂ granulate suitable for the process,
and an article of opaque quartz glass.**

Abstract

In a known process for the production of opaque quartz glass a blank is formed from synthetic SiO₂ granulate and is heated at a vitrification temperature to form a body of opaque quartz glass. In order to provide on this basis a process for the production of pure opaque quartz glass with a homogenous pore distribution, high density, high viscosity and a low tendency to devitrify, it is proposed according to the invention that the SiO₂ granulate to be used is a SiO₂ granulate (21; 31) composed of at least partially porous agglomerates of SiO₂ primary particles, with a specific BET surface ranging from 1.5 m²/g to 40 m²/g and an apparent density of at least 0.8 g/cm³. A SiO₂ granulate (21; 31) suitable for the implementation of the process is distinguished in that it is formed from at least partially porous agglomerates of SiO₂ primary particles and in that it has a specific BET surface ranging from 1.5 m²/g to 40 m²/g and an apparent density of at least 0.6 g/cm³.

(Fig.2)

